

EVG Technology Day

in HSINCHU, Taiwan November 20, 2019

Schedule

Wednesday, Nov. 20, 2019 08:00 - 16:00 hrs EVG Technology Day

Location

Hsinchu Ambassador Hotel 188 Chung Hwa Road Section 2

EVG Speaker

Paul Lindner Executive Technology Director

Frank Bögelsack
Product Manager

Christine Thanner Technology Development

Cindy Lee Technology Development & IP Manager Taiwan

Guest Speaker



In cooperation with

EVG OINTECH 億合科技

Register

For more information and to register for free:

www.EVGroup.com/events

Artificial Intelligence and Augmented Reality: Need for Innovative Manufacturing Solutions

Agenda

08:00	Registration - Our Experts Will Be Available for a Coffee and Chat!
09:00	Keynote: Yole Développement
Lithography Trends for Advanced Packaging	
09:30	Applications & Trends in Advanced Packaging
09:35	Status and Technology Update Temporary Bonding
10:05	Technology Announcement: EVG Maskless Exposure
10:35	Coffee Break
3D Integration and Heterogeneous Integration	
10:55	Applications & Trends in 3D and Heterogeneous Integration
11:00	Hybrid Bonding for Die Partitioning and Memory Integration
11:30	Next Generation Devices Scaling and Backside Power Distribution Enabled by Bondscale™
11:40	Metrology Needs for Heterogeneous Integration
11:55	Invited Lunch
NILPhotonics [®] for 3D Sensing and Augmented Reality	
NILPhoto	nics" for 3D Sensing and Augmented Reality
NILPhoto 13:10	Trends & Recent Developments in Photonics and Micro Optics
13:10	Trends & Recent Developments in Photonics and Micro Optics
13:10 13:15	Trends & Recent Developments in Photonics and Micro Optics SmartNIL® Nanoimprint Lithography - Transition to 300 mm Volume Manufacturing
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